PATENT COOPERATION TREATY

PCT

REC'D	27	JAN	2006
WIPO			PCT

INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

(Chapter II of the Patent Cooperation Treaty)

(PCT Article 36 and Rule 70)

Applicant's or agent's file reference TJ0405-PCT	FOR FURTHER ACT	ION	See Form PCT/IPEA/416				
International application No.	International filing date (da	y/month/year)	Priority date (day/month/yea	ar)			
PCT/JP2004/015328	08.10.2004		20.10.2003				
International Patent Classification (IPC) or national classification and IPC H01L27/06, H01L27/088, H01L21/762, H01L21/8234							
Applicant TOYOTA JIDOSHA KABUSHIKI KAISHA et al.							
This report is the international pre- Authority under Article 35 and trans	ismitted to the applicant	according to Article	his International Preliminary 36.	Examining			
2. This REPORT consists of a total of				1			
3. This report is also accompanied b	y ANNEXES, comprising	:					
a. 🛭 sent to the applicant and to	o the International Burea	u) a total of 5 shee	ts, as follows:	·			
sheets of the description and/or sheets containst Administrative Instruct	sheets of the description, claims and/or drawings which have been amended and are the basis of this report and/or sheets containing rectifications authorized by this Authority (see Rule 70.16 and Section 607 of the						
beyond the disclosure Supplemental Box.	sheets which supersede earlier sheets, but which this Authority considers contain an amendment that goes beyond the disclosure in the international application as filed, as indicated in item 4 of Box No. I and the						
b. (sent to the International Bureau only) a total of (indicate type and number of electronic carrier(s)), containing a sequence listing and/or tables related thereto, in computer readable form only, as indicated in the Supplemental Box Relating to Sequence Listing (see Section 802 of the Administrative Instructions).							
				• }			
4. This report contains indications re	elating to the following ite	ms:					
☐ Box No. I Basis of the op	inion						
☐ Box No. II Priority							
☐ Box No. III Non-establishm	nent of opinion with regar	d to novelty, inventi	ive step and industrial applica	ability			
☐ Box No. IV Lack of unity of							
M Pay No. V Pageoned state	ement under Article 35(2) tations and explanations) with regard to nove supporting such sta	elty, inventive step or industri tement	ial			
☑ Box No. VI Certain docum							
☐ Box No. VII Certain defects	s in the international appl	cation	. •				
☐ Box No. VIII Certain observ	ations on the internationa	al application					
		Dala of	of this report				
Date of submission of the demand		Date of completion of	n uns report				
08.08.2005		25.01.2006					
Name and mailing address of the international preliminary examining authority:		Authorized Officer	·	September Comments . E			
European Patent Office D-80298 Munich	Bernabé Prieto,	Α					
Tel. +49 89 2399 - 0 Tx: 523	3656 epmu d	Telephone No. +49					
Fax: +49 89 2399 - 4465		i elepnone No. +49	03 2033-2224	ogge eagle .			

INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

International application No. PCT/JP2004/015328

_	Box	x No. I Basis of the report				
1.	With filed	h regard to the language, this d, unless otherwise indicated	s report is based on the international application in the language in which it was under this item.			
		This report is based on translations from the original language into the following language, which is the language of a translation furnished for the purposes of:				
		 ☐ international search (under Rules 12.3 and 23.1(b)) ☐ publication of the international application (under Rule 12.4) ☐ international preliminary examination (under Rules 55.2 and/or 55.3) 				
2.	hav	th regard to the elements* of ve been furnished to the recei nort as "originally filed" and are	the international application, this report is based on (replacement sheets which ving Office in response to an invitation under Article 14 are referred to in this is not annexed to this report):			
C	Des	scription, Pages				
	1-31	1	as originally filed			
	Clai	ims, Numbers				
	1-14	4	as originally filed			
Dı	Dra	wings, Sheets				
	1/16	6-16/16	as originally filed			
		a sequence listing and/or an	y related table(s) - see Supplemental Box Relating to Sequence Listing			
з. С						
		☐ the description, pages ☐ the claims, Nos.				
		☐ the drawings, sheets/figs☐ the sequence listing (spe				
		any table(s) related to se				
4.		☐ This report has been established as if (some of) the amendments annexed to this report and listed below had not been made, since they have been considered to go beyond the disclosure as filed, as indicated in the Supplemental Box (Rule 70.2(c)).				
		☐ the description, pages☐ the claims, Nos.				
		☐ the drawings, sheets/figs				
		☐ the sequence listing (spe ☐ any table(s) related to se				
	*	•	ome or all of these sheets may be marked "superseded "			

INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY

International application No. PCT/JP2004/015328

Box No. V Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

4-14

1. Statement

Novelty (N) Yes: Claims

No: Claims 1-3

Inventive step (IS) Yes: Claims

No: Claims 1-14

Industrial applicability (IA) Yes: Claims 1-14

No: Claims

2. Citations and explanations (Rule 70.7):

see separate sheet

Box No. VI Certain documents cited

 Certain published documents (Rule 70.10) and /or

2. Non-written disclosures (Rule 70.9)

see separate sheet

The following comments relate to items of the cover sheet where the corresponding cases have been crossed, as well as to eventual aspects concerning the form and content of the application and clarity of the claims.

- 1 Reference is made to the following documents:
 - D1: US 2002/043699 A1 (AKIYAMA HAJIME) 18 April 2002 (2002-04-18)
 - D2: GB-A-2 310 081 (INTERNATIONAL RECTIFIER CORPORATION) 13 August 1997 (1997-08-13)
- The amendments filed with the letter of 05.08.2005 introduce subject-matter which extends beyond the disclosure of the international application as filed, contrary to Article 34(2)(b) PCT. The amendments concerned are the following:
- 2.1 In claim 1 (cf. lines 7-9) "a structure to separate ... " is now defined, which includes any type of structure, beyond the (at least one) trench filled with insulating material disclosed in the application as filed.
- 2.2 In claim 1 (cf. line 14) the wording "at least an output" appears to relate to a relay (NMOS and PMOS with their connection) as described in the description and figures but without its features, the non-inclusion of which in claim 1 results in an undue intermediate generalisation of its subject-matter.
- 2.3 In claim 4 (cf. lines 2-3), the newly introduced feature that "the high withstand voltage separating region surrounds ... regions" appears to be an undue generalisation of the features of claim 6 (one region (high or low voltage) surrounds the other and the withstand region is between and has a ring shape). Furthermore, the feature that the insulating partition is filled with insulating material in a trench has been removed, contrary to the requirements of Article 34(2)(b) PCT.
- 2.4 The removal from originally filed claims 12 and 13, on which present claims 12 and 13 are presently based, of the features " a plurality of fourth regions arranged in a ring shape ... first and second regions" results in an undue intermediate

generalisation of their subject-matter.

- 2.5 For the reasons explained above claims 1, 4, 12 and 13 are not admissible.
- 3 The present application does not comply with Article 33(2) PCT because the subjectmatter of claims 1-3, insofar as they are admissible (cf. item 2 above), is not new.
- 3.1 The subject-matter of independent claim 1 is fully anticipated by the content of document D1 (cf. Figures 16-17 and associated text), which discloses semiconductor device having a high voltage region (HR), a low voltage region (connected to D1), a high withstand voltage region (region therebetween, e. g. 620, 630, 640) separating the high voltage region and the low voltage region, a relay (NR, PR) in the high withstand voltage region (620, 630, 640), an insulating partition (620, 630, 640) having a trench filled with insulating material (601) between the relay and one of the high voltage and low voltage regions, an output wiring (SL1, G1, D1) between the relay and the high voltage region or low voltage region bridging over the insulating partition.

It should be further noted that: first, the relay of D1 has a source and gate connection at one side, and a drain at another, as in the present application (see NMOS and PMOS) (Article 33(2) PCT); second, even if the relay circuit of the present application is specified in the claims (which is not at present), this would only be an obvious design alternative, which the skilled person would use in accordance with the type of desired high-low transition (Article 33(3) PCT).

- 3.2 The additional technical features of dependent claims 2-3 are also already known from the disclosure of document D1 (cf. Figures 16-17 and associated text).
- The present application does not comply with Article 33(3) PCT because the subjectmatter of claims 4-14, as long as the claims are admissible, does not involve an inventive step.
- 4.1 The subject-matter of present claim 4 differs from the disclosure of document D1 (cf.

figures 16-17 and associated text) in that the relay is arranged to form a ring shape which separates the high and low voltage regions. The objective problem to be solved derivable therefrom and solution thereto is, however, already known from document D2 (cf. page 3, lines 13-18; figures 3-15). Thus, it would be obvious to the skilled person to use the teaching of D2 and provide in a device as disclosed in D1 a relay being arranged to form a ring shape which separates the high and low voltage regions. Therefore, the subject-matter of present claim 4 does not involve an inventive step.

- 4.2 The additional technical features of claims 5-14 (the features of claims 6, 7, 12 and 13 considered as dependent from claim 4) are obvious choices or modifications readily available to the skilled person. Therefore, the subject-matter of claims 5-14 does not involve an inventive step.
- 4.3 The possible advantage of an apparatus defined by a claim having a combination of features of present claims 1, 4 and 6 (without substrate and conductivity types), duly amended to be admissible (cf. item 2 above), is at present not clear vis-à-vis the combined teaching of the cited prior art.
- 5 The following deficiencies should also be noted:
- 5.1 Contrary to the requirements of Rule 5.1(a)(ii) PCT, the relevant background art disclosed in documents D1-D2 is not mentioned in the description, nor are these documents identified therein.
- 5.2 Independent claim 1 is not in the two-part form in accordance with Rule 6.3(b) PCT, which in the present case would be appropriate, with those features known in combination from the prior art being placed in a preamble (Rule 6.3(b)(i) PCT) and with the remaining features being included in a characterising part (Rule 6.3(b)(ii) PCT).
- 5.3 The features of the claims are not provided with reference signs placed in parentheses (Rule 6.2(b) PCT).

INTERNATIONAL PRELIMINARY REPORT ON PATENTABILITY (SEPARATE SHEET)

International application No.

PCT/JP2004/015328

5

10

15

20

CLAIMS

1. (Amended) A semiconductor apparatus containing a low potential reference circuit region and a high potential reference circuit region between which signals are transmitted, the semiconductor apparatus comprising:

a high withstand voltage separating region arranged between the low and high potential reference circuit regions, the high withstand voltage separating region including a separating structure to separate both potential reference circuit regions;

a relay semiconductor device, formed in the high withstand voltage separating region, for transmitting a signal from one of the low and high potential reference circuit regions to the other of them; and

an insulating partition arranged between at least an output one of the low and high potential reference circuit regions and the relay semiconductor device, the insulating partition being filled with insulating material in a trench,

wherein output wiring of the relay semiconductor device is wired to an output one of the low and high potential reference circuit regions bridging over the insulating partition.

- 2. (Unchanged) A semiconductor apparatus according to claim 1 further comprising a substrate region arranged below the low and high potential reference circuit regions, wherein
- 25 bottom portion of the insulating partition extends to the substrate region, and

the insulation partition surrounds the relay semiconductor device.

10

15

25

- 3. (Unchanged) A semiconductor apparatus according to claim 1 or claim 2 further comprising a group of insulating partitions arranged between the low and high potential reference circuit regions, the group of insulating partitions dividing space between the low and high potential reference circuit regions into plural regions.
- 4. (Amended) A semiconductor apparatus according to claim 1,

wherein the high withstand voltage separating region surrounds one of the low and high potential reference circuit regions,

a plurality of the relay semiconductor devices are arranged to form a ring shape in the high withstand voltage separating region,

each relay semiconductor device is surrounded with an insulating partition, and

output wiring of each relay semiconductor device is wired to an output one of the low and high potential reference circuit regions bridging over the insulating partition.

- 5. (Unchanged) A semiconductor apparatus according to claim 1 or claim 4 further comprising:
- a substrate region arranged below the low and high potential reference circuit regions; and

an insulating layer embedded between the low and high potential reference circuit regions and the substrate region, the insulating layer electrically insulating the low and high potential reference circuit regions from the substrate region,

wherein bottom portions of the insulating partitions extend to the insulating layer and the insulation partitions surround the relay semiconductor devices. 10

20

6. (Amended) A semiconductor apparatus according to claim 1 comprising:

a semiconductor substrate of first conduction type;

wherein the low and high potential reference circuit regions are regions of second conduction type formed on a main surface of the semiconductor substrate so that one of the regions surrounds the other in separated relation, and

the high withstand voltage separating region is a region formed in a ring shape between the low and high potential reference circuit regions.

7. (Amended) A semiconductor apparatus according to claim 1 comprising:

a semiconductor substrate of either first or second conduction

15 type; and

an insulating film formed on the semiconductor substrate;
wherein the low and high potential reference circuit regions
are regions of second conduction type formed on the insulating film
so that one of the regions surrounds the other in separated relation,
and

the high withstand voltage separating region is a region formed in a ring shape between the low and high potential reference circuit regions.

25 8. (Unchanged) A semiconductor apparatus according to claim 6 or claim 7, wherein

bottom portion of the insulating partition extends to either the semiconductor substrate or the insulating film, and

the insulating partition surrounds periphery of a relay.

13. A semiconductor apparatus according to claim 1 comprising: a semiconductor substrate of either first or second conduction type; and

an insulating film formed on the semiconductor substrate;

wherein the low and high potential reference circuit regions are regions of second conduction type formed on the insulating film so that one of the regions surrounds the other in separated relation.

14. (Unchanged) A semiconductor apparatus according to claim 12

10 or claim 13, wherein

bottom portion of the insulating partition extends to either the semiconductor substrate or the insulating film, and

the insulating partition surrounds periphery of a relay semiconductor device in a fourth region from at least three directions.